

Electronic properties and interface contact of graphene/CrSiTe₃ van der Waals heterostructures

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Table S1(a) Magnetic moment of atoms in the of graphene/CrSiTe₃ at $d=3.19 \text{ \AA}$

| direction | Cr | Si | Te |
|-------------|--------------|--------------|---------------|
| In plane | $3.38 \mu_B$ | $0.010\mu_B$ | $0.102\mu_B$ |
| Z direction | $0.02 \mu_B$ | $0.001\mu_B$ | $-0.010\mu_B$ |

Table S1(b) Magnetic moment of atoms in the of graphene/CrSiTe₃ at $d=2.75 \text{ \AA}$

| direction | Cr | Si | Te |
|-------------|---------------|---------------|----------------|
| In plane | $2.82 \mu_B$ | $0.001\mu_B$ | $0.062\mu_B$ |
| Z direction | $-0.68 \mu_B$ | $-0.004\mu_B$ | $-0.028 \mu_B$ |

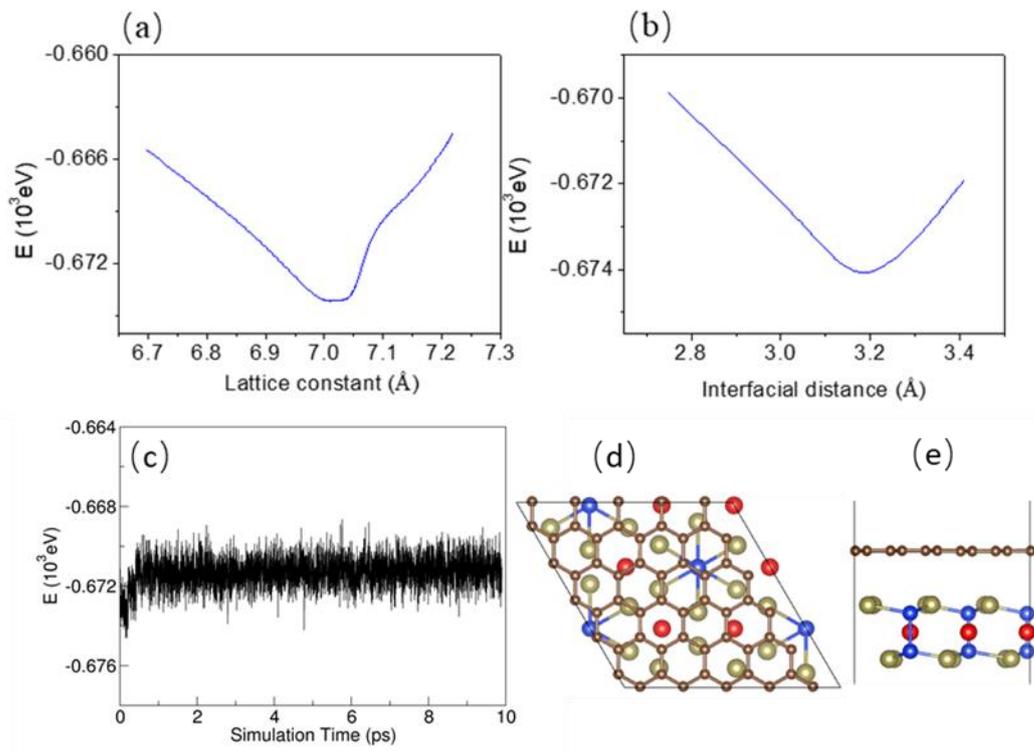


Fig. S1 (a) The calculated total energy of the Gr/CrSiTe₃ heterostructure as a function of the lattice constant of CrSiTe₃; (b) The calculated total energy of the Gr/CrSiTe₃ heterostructure as a function of the interfacial distance; (c) Ab initio molecular dynamics simulations of Gr/CrSiTe₃ at 300 K; (d) and (e) the final structure after 10 ps, showing that the Graphene/CrSiTe₃ heterostructure remains stable.

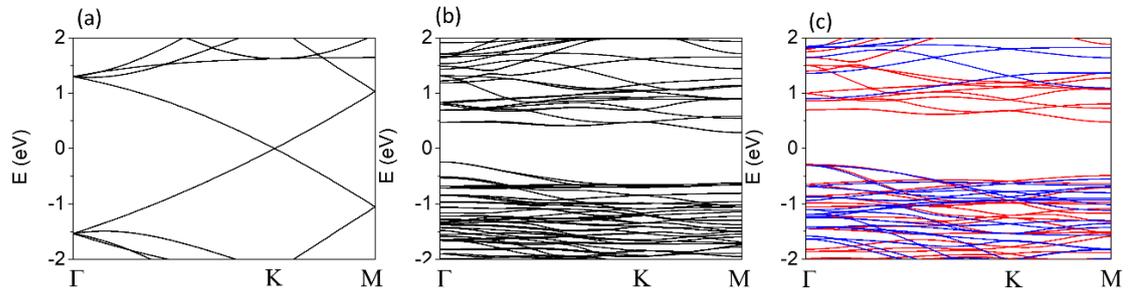


Fig. S2 (a) Band structures of graphene; (b) Band structures of CrSiTe₃ ML with SOC interaction and (c) The spin-polarized band structure of the CrSiTe₃ ML, red for spin-up and blue for spin-down.

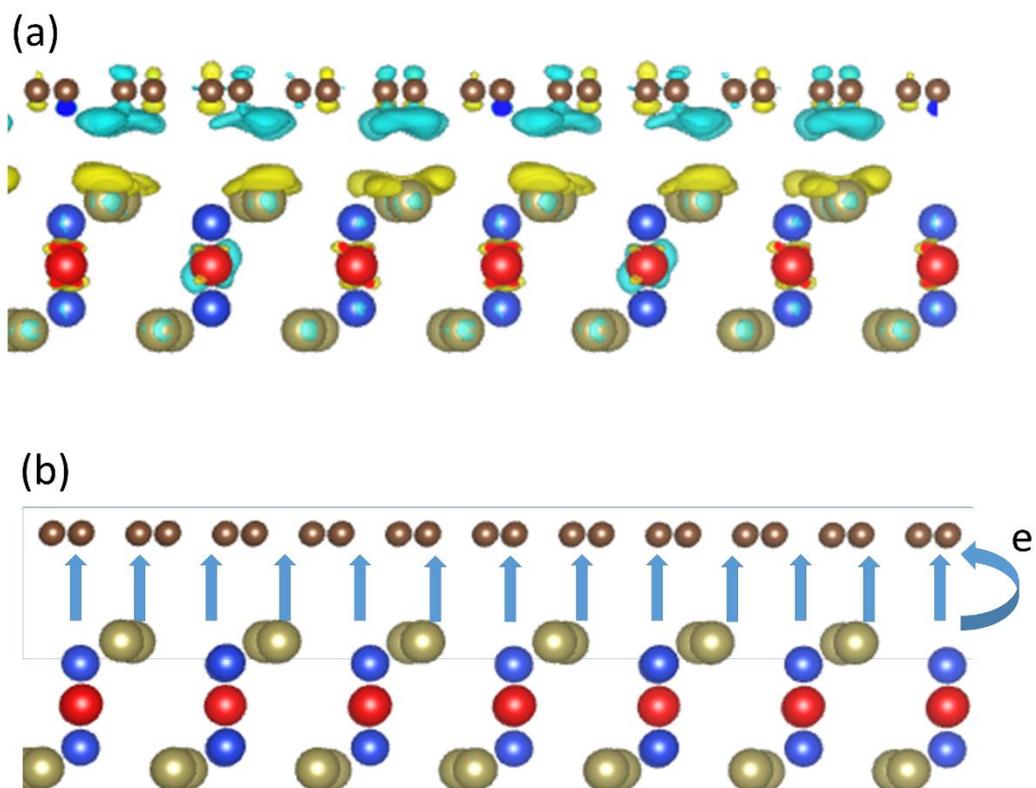


Fig. S3 (a) Charge density difference of the graphene/CrSiTe₃ at the interfacial distance $d=2.75 \text{ \AA}$. The isosurface refers to isovalues of $0.001 e \text{ \AA}^{-3}$. (b) Schematic diagram of the built-in electric field at the graphene/CrSiTe₃ interface.

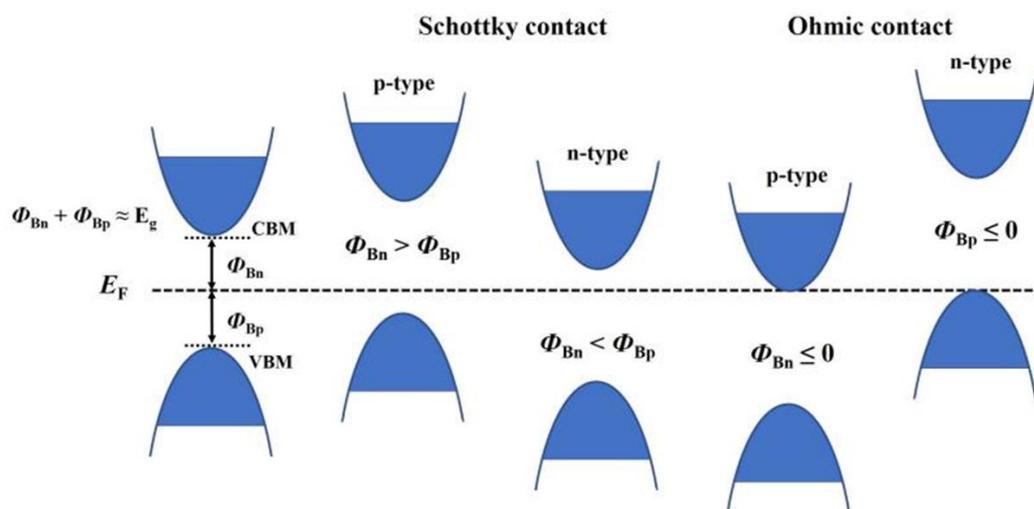


Fig. S4 Diagrammatic illustration of the p-type and n-type Schottky and Ohmic contact at the interface region.

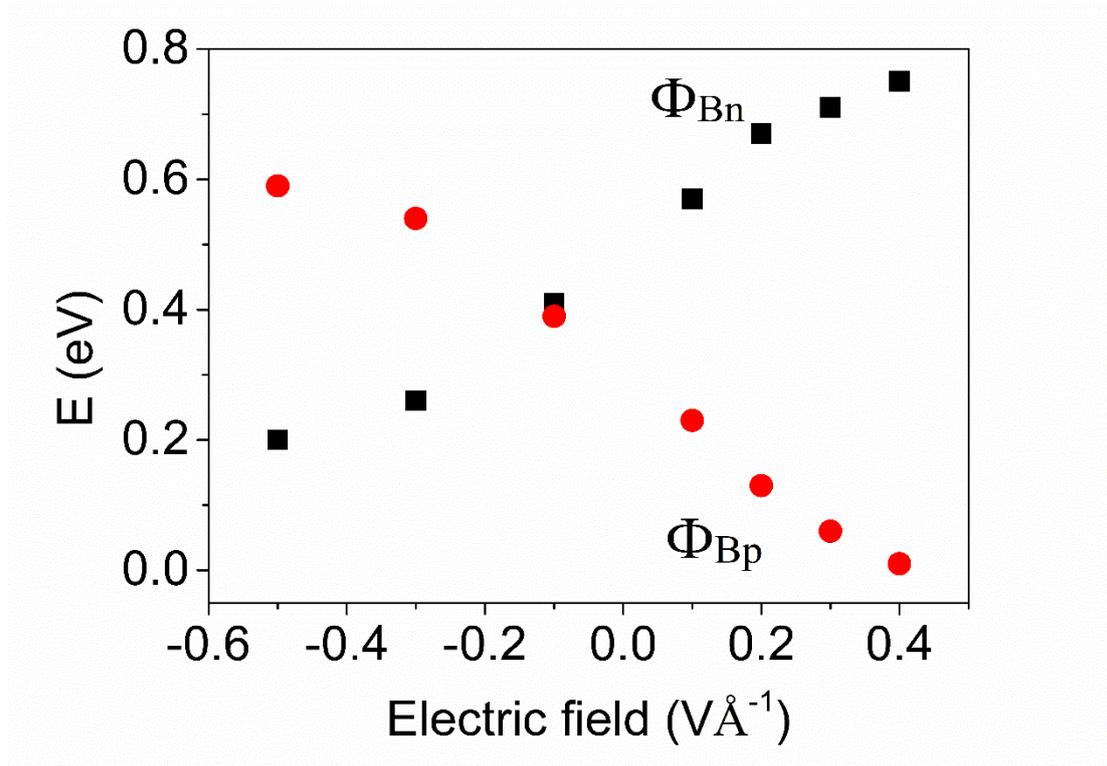


Fig. S5 The SBH of the graphene/CrSiTe₃ as a function of the external electric field. The n-type Schottky barrier (Φ_{Bn}) noted in black color is the energy difference between the E_{CBM} and the E_F , while the p-type Schottky barrier (Φ_{Bp}) noted in red color is the energy difference between the E_F and the E_{VBM} .